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## (54) PREPARATION FOR EXTERNAL USE FOR SKIN

### (57)Abstract:

**PROBLEM TO BE SOLVED:** To obtain a preparation for external use for skin that has the action to inhibit the damage of dermal fibroblast cells by ultraviolet rays; prevents the formation of peroxy lipid caused by the occurrence of active oxygen in the skin and is effective for the prevention and improvement of the symptoms such as occurrence of wrinkles or deterioration in skin elasticity; and has the effect for preventing or improving the formation of peroxide lipids caused by the occurrence of active oxygen in the skin, to prevent and improve skin inflammation and roughening.

**SOLUTION:** One or more kinds selected from an extract from Agaricus mushroom fruits and the filtrate of the mycelium culture are combined with an active oxygen scavenger and they are formulated to a preparation for external use for skin. As an active oxygen scavenger, is preferably used an extract from plants having the action to scavenge active oxygen, for example, Hamamelis, Quercus, Aesculus, Sanguisorba, Paeonia, Ginkgo bibloba L., Betulaceae tree, parsley (Petroselinum sativum or the like); additionally, carotenoid, flavonoid, tannin, superoxide dismutase, gallic acid and its salts or derivatives, hydroquinone, thioredoxin, thioredoxin reductase and the like.

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